IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: GEUN-YOUNG YEOM, ET AL.

FOR: LAYER-BY-LAYER ETCHING APPARTUS USING NEUTRAL BEAM AND METHOD OF ETCHING USING THE SAME

PRELIMINARY AMENDMENT

The Assistant Commissioner of Patents and Trademarks Washington, DC 20231

Dear Sir:

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Prior to the Examiner acting in the above-referenced application, please preliminary amend the claims as follows:

IN THE CLAIMS:

Please replace claims 1-4, 7-11 and 14-15 with the following re-written clean version.

1. (Amended) A layer-by-layer etching apparatus using a neutral beam, the layer-by-layer etching apparatus comprising:

a reaction chamber having a stage therein on which a substrate to be etched is mounted;

a neutral beam generator for generating a neutral beam from a source gas to supply the neutral beam into the reaction chamber;

a shutter disposed between the neutral beam generator and the reaction chamber, for controlling the supply of the neutral beam into the reaction chamber;

an etching gas supply for supplying an etching gas into the reaction chamber; a purge gas supply for supplying a purge gas into the reaction chamber; and

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